L Number	Hits	Search Text	DB	Time stamp
1	. 1547	(427/552,553,555,558).CCLS.	USPAT;	2004/08/16 09:26
2	1093	(427/226).CCLS.	US-PGPUB USPAT;	2004/08/16 09:26
3	2172	(427/248.1,255.18,255.23).CCLS.	US-PGPUB USPAT; US-PGPUB	2004/08/16 09:26
4	3565	(427/256,259,270,271,272,282).CCLS.	USPAT; US-PGPUB	2004/08/16 09:27
5	552	(117/88,95).CCLS.	USPAT; US-PGPUB	2004/08/16 09:27
6	271	(438/503,507).CCLS.	USPAT; US-PGPUB	2004/08/16 09:27
7	245	(423/349).CCLS.	USPAT; US-PGPUB	2004/08/16 09:27
8	1161	(118/726).CCLS.	USPAT; US-PGPUB	2004/08/16 09:27
9	10032	((427/552,553,555,558).CCLS.) ((427/226).CCLS.) ((427/248.1,255.18,255.23).CCLS.) ((427/256,259,270,271,272,282).CCLS.) ((117/88,95).CCLS.) ((438/503,507).CCLS.) ((423/349).CCLS.) ((118/726).CCLS.)	USPAT; US-PGPUB	2004/08/16 09:27
-10	3	((427/552,553,555,558).CCLS.) and ((silicon or Si) near4 (coat\$3 or film or layer or deposit\$3 or grow\$3 or \$4CVD)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or (cyclical adj silane) or (cyclo adj silane) or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj pentasilane) or (cyclo adj pentasilane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2	USPAT;	2004/08/16-09:35-
11	0	cyclopentasilane)) ((427/226).CCLS.) and ((silicon or Si) near4 (coat\$3 or film or layer or deposit\$3 or grow\$3 or \$4CVD)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or (cyclical adj silane) or (cyclo adj silane) or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))	USPAT; US-PGPUB	2004/08/16 09:32
12	10		USPAT; US-PGPUB	2004/08/16 09:33

13	0	((427/256,259,270,271,272,282).CCLS.) and ((silicon or Si) near4 (coat\$3 or film or	USPAT; US-PGPUB	2004/08/16 09:33
		layer or deposit\$3 or grow\$3 or \$4CVD)) and ((ring adj silane) or (cyclic adj		
		silane) or cyclosilane or (cyclical adj		
		silane) or (cyclo adj silane) or		
		cyclopentasilane or Si5H10 or "Si.sub.5		
		H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj		
		silane) or silylcyclopentasilane or Si6H12		
		or "Si.sub.6H.sub.12" or "Si.sub.6		·
		H.sub.12" or (silyl near2		
14	1	cyclopentasilane)) ((117/88,95).CCLS.) and ((silicon or Si)	USPAT;	2004/08/16 09:33
111		near4 (coat\$3 or film or layer or	US-PGPUB	
		deposit\$3 or grow\$3 or \$4CVD)) and ((ring		
		adj silane) or (cyclic adj silane) or cyclosilane or (cyclical adj silane) or		
	Ì	(cyclo adj silane) or cyclopentasilane or		
		Si5H10 or "Si.sub.5 H.sub.10" or		
		"Si.sub.5H.sub.10" or (cyclo adj		
		pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12		
		or "Si.sub.6H.sub.12"-or "Si.sub.6-		
	1	H.sub.12" or (silyl near2		
15	0	cyclopentasilane)) ((438/503,507).CCLS.) and ((silicon or	USPAT;	2004/08/16 09:33
13	"	Si) near4 (coat\$3 or film or layer or	US-PGPUB	
		deposit\$3 or grow\$3 or \$4CVD)) and ((ring		
		adj silane) or (cyclic adj silane) or cyclosilane or (cyclical adj silane) or		
		(cyclo adj silane) or cyclopentasilane or	ļ	
		Si5H10 or "Si.sub.5 H.sub.10" or	1	
		"Si.sub.5H.sub.10" or (cyclo adj		
		pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12		
		or "Si.sub.6H.sub.12" or "Si.sub.6		
		H.sub.12" or (silyl near2		
16	0	cyclopentasilane)) ((423/349).CCLS.) and ((silicon or Si)	USPAT;	2004/08/16 09:34
16	\ \ \ \ \ \ \ \ \ \ \ \ \ \ \ \ \ \ \	near4 (coat\$3 or film or layer or	US-PGPUB	2001/00/10 03:31
		deposit\$3 or grow\$3 or \$4CVD)) and ((ring		
		adj silane) or (cyclic adj silane) or		
		cyclosilane or (cyclical adj silane) or (cyclo adj silane) or cyclopentasilane or		
		Si5H10 or "Si.sub.5 H.sub.10" or		
		"Si.sub.5H.sub.10" or (cyclo adj		
		pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12		
		or "Si.sub.6H.sub.12" or "Si.sub.6		
		H.sub.12" or (silyl near2		
17	0	cyclopentasilane)) ((423/349).CCLS.) and ((ring adj silane)	USPAT;	2004/08/16 09:34
17	1	or (cyclic adj silane) or cyclosilane or	US-PGPUB	2004,00710 07.34
		(cyclical adj silane) or (cyclo adj		
		silane) or cyclopentasilane or Si5H10 or		
		"Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj		
		penta adj silane) or silylcyclopentasilane		
		or Si6H12 or "Si.sub.6H.sub.12" or		}
		"Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))		
1	_ f	1 - 4 E		<u> </u>

,				
18	0	((118/726).CCLS.) and ((silicon or Si)	USPAT;	2004/08/16 09:34
		near4 (coat\$3 or film or layer or	US-PGPUB	
		deposit\$3 or grow\$3 or \$4CVD)) and ((ring		
		adj silane) or (cyclic adj silane) or		
		cyclosilane or (cyclical adj silane) or		
		(cyclo adj silane) or cyclopentasilane or		
		Si5H10 or "Si.sub.5 H.sub.10" or		
		"Si.sub.5H.sub.10" or (cyclo adj		
		pentasilane) or (cyclo adj penta adj		
		silane) or silylcyclopentasilane or Si6H12		
		or "Si.sub.6H.sub.12" or "Si.sub.6		
		H.sub.12" or (silyl near2		
		cyclopentasilane))		
19	0	((118/726).CCLS.) and ((ring adj silane)	USPAT;	2004/08/16 09:34
		or (cyclic adj silane) or cyclosilane or	US-PGPUB	2004/08/18 09:34
		(cyclical adj silane) or (cyclo adj	03-FGF0B	
		silane) or cyclopentasilane or Si5H10 or		
		"Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10"	Ī	
		or (cyclo adj pentasilane) or (cyclo adj		1
		penta adj silane) or silylcyclopentasilane		
		or Si6H12 or "Si.sub.6H.sub.12" or		
				1
		"Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))		
20	14			
20		(((427/552,553,555,558).CCLs.)		-2004/08/16-10:-19
		((427/226).CCLS.)	US-PGPUB	
ĺ		((427/248.1,255.18,255.23).CCLS.)		
		((427/256,259,270,271,272,282).CCLS.)		
		((117/88,95).CCLS.) ((438/503,507).CCLS.)		
		((423/349).CCLS.) ((118/726).CCLS.)) and		
		((ring adj silane) or (cyclic adj silane)		
		or cyclosilane or (cyclical adj silane) or		
		(cyclo adj silane) or cyclopentasilane or		
		Si5H10 or "Si.sub.5 H.sub.10" or		
		"Si.sub.5H.sub.10" or (cyclo adj		
		pentasilane) or (cyclo adj penta adj		
ļ		silane) or silylcyclopentasilane or Si6H12		
Ì		or "Si.sub.6H.sub.12" or "Si.sub.6		
		H.sub.12" or (silyl near2		
		cyclopentasilane))		

21		/ ///27/EE2 EE2 EEE EE0\ COTC \	HCDATT-	2004/00/16 00 05
21	0	( (((427/552,553,555,558).CCLS.) ((427/226).CCLS.)	USPAT; US-PGPUB	2004/08/16 09:35
		((427/248.1,255.18,255.23).CCLS.)	05 19105	
		((427/256,259,270,271,272,282).CCLS.)		
]		((117/88,95).CCLS.) ((438/503,507).CCLS.)		
		((423/349).CCLS.) ((118/726).CCLS.)) and		
		((ring adj silane) or (cyclic adj silane)		
		or cyclosilane or (cyclical adj silane) or		
		(cyclo adj silane) or cyclopentasilane or		
		Si5H10 or "Si.sub.5 H.sub.10" or		
		"Si.sub.5H.sub.10" or (cyclo adj		
		pentasilane) or (cyclo adj penta adj		
		silane) or silylcyclopentasilane or Si6H12		<u> </u>
		or "Si.sub.6H.sub.12" or "Si.sub.6		1
		H.sub.12" or (silyl near2		
		cyclopentasilane))) not ((		
		((427/552,553,555,558).CCLS.) and		
		((silicon or Si) near4 (coat\$3 or film or		
		layer or deposit\$3 or grow\$3 or \$4CVD))		<b>!</b>
		and ((ring adj silane) or (cyclic adj		
		silane) or cyclosilane or (cyclical adj		
		silane) or (cyclo adj silane) or		
		cyclopentasilane or Si5H10 or "Si.sub.5		
		H.sub.10" or "Si.sub.5H.sub.10" or (cyclo		
		adj pentasilane) or (cyclo adj penta adj	1	1
		silane) or silylcyclopentasilane or Si6H12		]
		or "Si.sub.6H.sub.12" or "Si.sub.6		1
		<pre>H.sub.12" or (silyl near2 cyclopentasilane))) or (</pre>		
		((427/248.1,255.18,255.23).CCLS.) and		·
		((silicon or Si) near4 (coat\$3 or film or		
<u> </u>		layer or deposit\$3 or grow\$3 or \$4CVD))		İ
		and ((ring adj silane) or (cyclic adj		
		silane) or cyclosilane or (cyclical adj		
		silane) or (cyclo adj silane) or		
		cyclopentasilane or Si5H10 or "Si.sub.5		1
		H.sub.10" or "Si.sub.5H.sub.10" or (cyclo		[
		adj pentasilane) or (cyclo adj penta adj		,
		silane) or silylcyclopentasilane or Si6H12		
		or "Si.sub.6H.sub.12" or "Si.sub.6		
		H.sub.12" or (silyl near2		
		cyclopentasilane))) or (		
		((117/88,95).CCLS.) and ((silicon or Si)		
		near4 (coat\$3 or film or layer or		
		deposit\$3 or grow\$3 or \$4CVD)) and ((ring		
		adj silane) or (cyclic adj silane) or		
		cyclosilane or (cyclical adj silane) or		
		(cyclo adj silane) or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or		
		"Si.sub.5H.sub.10" or (cyclo adj		
		pentasilane) or (cyclo adj penta adj		
		silane) or silylcyclopentasilane or Si6H12	1	
		or "Si.sub.6H.sub.12" or "Si.sub.6		]
		H.sub.12" or (silyl near2		
		cyclopentasilane))))		
22	41	((silicon or Si or polysilicon) near4	EPO; JPO;	2004/08/16 09:43
		(coat\$3 or film or layer or deposit\$3 or	DERWENT;	
		grow\$3 or \$4CVD)) and ((ring adj silane)	IBM TDB	
		or (cyclic adj silane) or cyclosilane or	_	
		(cyclical adj silane) or (cyclo adj		·
		silane) or cyclopentasilane or Si5H10 or		
		"Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10"		
<u> </u>		or (cyclo adj pentasilane) or (cyclo adj		
		penta adj silane) or silylcyclopentasilane		
		or Si6H12 or "Si.sub.6H.sub.12" or		
		"Si.sub.6 H.sub.12" or (silyl near2		
L		cyclopentasilane))		

23	8	(((silicon or Si or polysilicon) near4 (coat\$3 or film or layer or deposit\$3 or grow\$3 or \$4CVD)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or (cyclical adj silane) or (cyclo adj silane) or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))) and (inactive or SAM or monolayer or active or ((mono or	EPO; JPO; DERWENT; IBM_TDB	2004/08/16 09:44
		molecular) adj (layer or film)) or (self	-	
		adj assembl\$4) or mask\$3 or pattern\$3 or selectively)		
24	33	<pre>(((silicon or Si or polysilicon) near4 (coat\$3 or film or layer or deposit\$3 or grow\$3 or \$4CVD)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or (cyclical adj silane) or (cyclo adj silane) or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj</pre>	EPO; JPO; DERWENT; IBM_TDB	2004/08/16 09:39
		penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))) not ((((silicon or Si or polysilicon) near4 (coat\$3 or film or layer or deposit\$3 or grow\$3 or \$4CVD)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or (cyclical adj silane) or (cyclo adj silane) or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5 H.sub.10" or (cyclo adj pentasilane) or (cyclo adj pentasilane) or (cyclo adj pentasilane) or (cyclo adj pentasilane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))) and (inactive or SAM or monolayer or active or ((mono or molecular) adj (layer or film)) or (self adj assembl\$4) or mask\$3 or pattern\$3 or selectively))		
25	168		USPAT; US-PGPUB	2004/08/16 09:43
26	133	(((silicon or Si or polysilicon) near4 (coat\$3 or film or layer or deposit\$3 or grow\$3 or \$4CVD)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or (cyclical adj silane) or (cyclo adj silane) or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5 H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))) and (inactive or SAM or monolayer or active or (mono or molecular) adj (layer or film)) or (self adj assembl\$4) or mask\$3 or pattern\$3 or selectively)	USPAT; US-PGPUB	2004/08/16 09:44

27	133		USPAT;	2004/08/16 09:55
		(coat\$3 or film or layer or deposit\$3 or	US-PGPUB	
		grow\$3 or \$4CVD)) and ((ring adj silane)		
		or (cyclic adj silane) or cyclosilane or		
		(cyclical adj silane) or (cyclo adj		
		silane) or cyclopentasilane or Si5H10 or		
		"Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10"		
		or (cyclo adj pentasilane) or (cyclo adj		
		penta adj silane) or silylcyclopentasilane		
		or Si6H12 or "Si.sub.6H.sub.12" or		
ĺ		"Si.sub.6 H.sub.12" or (silyl near2		
		cyclopentasilane))) and (inactive or SAM		
l		or monolayer or active or ((mono or		
		molecular) adj (layer or film)) or (self		
	,	adj assembl\$4) or mask\$3 or pattern\$3 or		<b>j</b>
		selectively or photomask\$3)		
28	35	(((silicon or Si or polysilicon) near4	USPAT;	2004/08/16 09:58
		(coat\$3 or film or layer or deposit\$3 or	US-PGPUB	
		grow\$3 or \$4CVD)) and ((ring adj silane)		
		or (cyclic adj silane) or cyclosilane or		
		(cyclical adj silane) or (cyclo adj		
		silane) or cyclopentasilane or Si5H10 or		
		"Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10"		
		or (cyclo adj pentasilane) or (cyclo adj		
		penta adj silane) or silylcyclopentasilane		
		or Si6H12 or "Si.sub.6H.sub.12" or		
		"Si.sub.6 H.sub.12" or (silyl near2		
		cyclopentasilane))) not ((((silicon or Si		
		or polysilicon) near4 (coat\$3 or film or		
		layer or deposit\$3 or grow\$3 or \$4CVD))	-	
		and ((ring adj silane) or (cyclic adj		
		silane) or cyclosilane or (cyclical adj silane) or (cyclo adj silane) or		
		cyclopentasilane or Si5H10 or "Si.sub.5		
		H.sub.10" or "Si.sub.5H.sub.10" or (cyclo		
		adj pentasilane) or (cyclo adj penta adj		
		silane) or silylcyclopentasilane or Si6H12		
		or "Si.sub.6H.sub.12" or "Si.sub.6		
		H.sub.12" or (silyl near2		
İ		cyclopentasilane))) and (inactive or SAM		
		or monolayer or active or ((mono or		
		molecular) adj (layer or film)) or (self		:
		adj assembl\$4) or mask\$3 or pattern\$3 or		
		selectively or photomask\$3))		
29	2	(((427/552,553,555,558).CCLS.)	USPAT;	2004/08/16 09:59
		((427/226).CCLS.)	US-PGPUB	
		((427/248.1,255.18,255.23).CCLS.)		
		((427/256,259,270,271,272,282).CCLS.)		
		((117/88,95).CCLS.) ((438/503,507).CCLS.)		
		((423/349).CCLS.) ((118/726).CCLS.)) and		
		(active with inactive with (\$4CVD or		
		(vapor adj deposit\$3)))		
30	15	(active with inactive with (\$4CVD or	USPAT;	2004/08/16 10:00
22	1	(vapor adj deposit\$3)))	US-PGPUB	0004/00/16 00 =:
31	13	((active with inactive with (\$4CVD or	USPAT;	2004/08/16 09:59
		(vapor adj deposit\$3)))) not	US-PGPUB	
		((((427/552,553,555,558).CCLS.)		
		((427/226).CCLS.)		
		((427/248.1,255.18,255.23).CCLS.) ((427/256,259,270,271,272,282).CCLS.)		
		((427/256,259,270,271,272,282).CCLS.) ((117/88,95).CCLS.) ((438/503,507).CCLS.)		
		((423/349).CCLS.) ((438/303,307).CCLS.)		
		(active with inactive with (\$4CVD or		
		(vapor adj deposit\$3))))		
32	11	(active with inactive with (\$4CVD or	EPO; JPO;	2004/08/16 10:01
_		(vapor adj deposit\$3)))	DERWENT;	111, 30, 20 10, 01
			IBM TDB	
<u> </u>				L. — — — — — — — — — — — — — — — — — — —

33	147	((118/726).CCLS.) and ((crucible or	USPAT;	2004/08/16 10:17
		evaporator or source or substrate or	US-PGPUB	
		liquid or solution) near7 (pattern\$3 or		
		mask\$3 or SAM or photomask\$3 or monolayer		
		or ((mono or molecular) near2 (layer or		
		film)) or (self adj assembl\$3)))		
34	25898	((Si or silicon or polysilicon) near4	USPAT;	2004/08/16 10:23
		(coat\$3 or deposit\$3 or film or layer or	US-PGPUB;	
		grow\$3 or \$4CVD) with (\$4CVD or (vapor adj	EPO; JPO;	
		deposit\$3)) same (selective\$3 or pattern\$3	DERWENT;	
		or portion))	IBM_TDB	
35	253	(((Si or silicon or polysilicon) near4	USPAT;	2004/08/16 10:19
		(coat\$3 or deposit\$3 or film or layer or	US-PGPUB;	
		grow\$3 or \$4CVD) with (\$4CVD or (vapor adj	EPO; JPO;	
		deposit\$3)) same (selective\$3 or pattern\$3	DERWENT;	
		or portion))) and	IBM TDB	
		(((427/552,553,555,558).CCLS.)		
		((427/226).CCLS.)		
		((427/248.1,255.18,255.23).CCLS.)		
		((427/256,259,270,271,272,282).CCLS.)		
		((117/88,95).CCLS.) ((438/503,507).CCLS.)		
		((423/349).CCLS.) ((118/726).CCLS.))		
36	18	(((Si or silicon or polysilicon) near4	USPAT;	2004/08/16 10:20
		(coat\$3 or deposit\$3 or film or layer or	-US-PGPUB	
		grow\$3 or \$4CVD) with (\$4CVD or (vapor adj		
		deposit\$3)) same (selective\$3 or pattern\$3		
		or portion))) and ((ring adj silane) or		
		(cyclic adj silane) or cyclosilane or		
		(cyclical adj silane) or (cyclo adj		
		silane) or cyclopentasilane or Si5H10 or		
		"Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10"		
		or (cyclo adj pentasilane) or (cyclo adj		
		penta adj silane) or silylcyclopentasilane		
		or Si6H12 or "Si.sub.6H.sub.12" or		
		"Si.sub.6 H.sub.12" or (silyl near2		
		cyclopentasilane))		
37	21	(((Si or silicon or polysilicon) near4	USPAT;	2004/08/16 10:28
1		(coat\$3 or deposit\$3 or film or layer or	US-PGPUB;	
		grow\$3 or \$4CVD) with (\$4CVD or (vapor adj	EPO; JPO;	
		deposit\$3)) same (selective\$3 or pattern\$3	DERWENT;	
		or portion))) and ((deposit\$3 or apply\$3	IBM_TDB	
		or arrang\$3 or place or placed or placing		
		or print\$3) near4 (liquid or solution or		
		precursor or \$10silane) near4 (substrate		
		or base or crucible or evaporator or		
,		source or vaporizer or vaporizor) with		
l		(evaporat\$3 or vaporize))		
38	41	((deposit\$3 or apply\$3 or arrang\$3 or	USPAT;	2004/08/16 10:29
		place or placed or placing or print\$3)	US-PGPUB;	
		near4 (liquid or solution or precursor or	EPO; JPO;	
		\$10silane) near4 (substrate or base or	DERWENT;	
		crucible or evaporator or source or	IBM_TDB	
		vaporizer or vaporizor) with (evaporat\$3		
		or vaporize) with (pattern\$3 or		
i	l	selective\$3))	I	